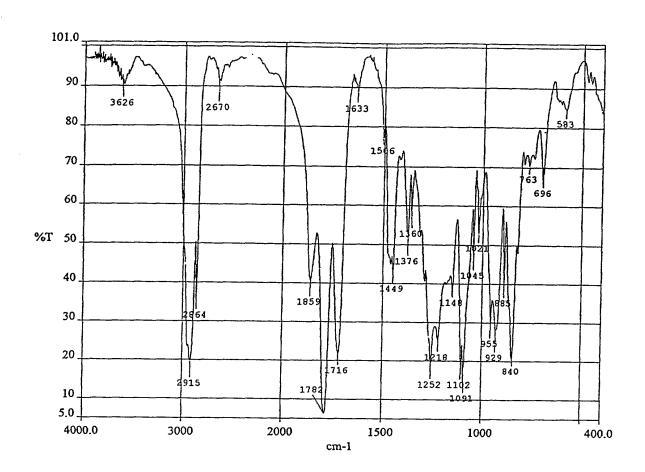
Inventor Name: Taeko IDEGAWA et al. Title of Invention: NOVEL COPOLYMER, PHOTORESIST COMPOSITION, AND PROCESS FOR FORMING RESIST PATTERN WITH HIGH ASPECT RATIO

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## FIG. 1



042815-2.PK

042815-2.SP 3601 4000.0 400.0 6.3 100.0 4.0 %T 8 3.0

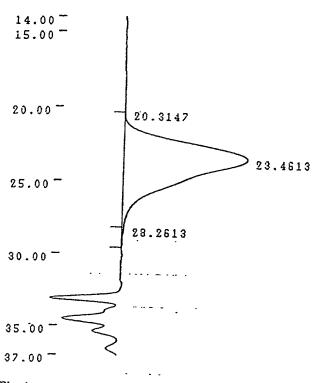
REF 4000 97.0 2000 88.8 600 3626.9 90.1 2915.5 19.9 2864.1 37.9 2670.0 91.1 1859.1 40.8 1782.3 6.3 1716.3 21.7 1633.7 88.8 1506.0 77.5 1449.8 42.9 1376.8 52.2 1360.3 57.1 1252.0 19.5 1218.2 25.2 1148.3 38.4 1102.8 18.0 1091.1 18.3 1045.0 48.6 1021.6 52.9 955.2 30.1 929.9 27.9 885.8 39.9 840.0 20.6 763.8 70.4 696.1 66.9 583.4 84.7

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FIG. 2



CHANNEL 1 METHOD 0,0,4,3

CALIBRATION OFF

NO. NAME  1 2	RET TIME 20.3147 23.4613 28.2613	AREA 96.1 2280773.8 7062.7 2287932.8	MARK ID#	CONC 96.1277	CONC %
3 TOTAL				M I 2 M I 3	7082.6992

CALIBRATION DATA

3 ORDER REGRESSION

LOG  $M = a*T^3+b*T^2+c*T^1+d$ 

a = -6.509859E-004 \_\_\_\_

b = 5.063016E-002

c = -1.552977E+000 d = 2.123975E+001

- PEAK TOP RT = 23.5750 : M = 17299 MN = 11243 . . МЫ = 18729 MW/MN = 1.6658 MZ =27080 MZ/MN = 2.4087